

AMENDMENTS TO THE CLAIMS

1-3. (Cancelled)

4. (Previously Presented) A method of etching and cleaning objects contained in a vessel, comprising the steps of:

introducing an etching solution into the vessel from below the objects;

etching the objects with the etching solution;

introducing a pressurized gas into the vessel from above the objects to force the etching solution out of the vessel from below the objects;

cleaning the objects by introducing a cleaning solution into the vessel from below the objects; and

draining the cleaning solution from the vessel from above the objects.

5. (Previously Presented) The method of claim 4, wherein the sequential steps of forcing out the etching solution alone and draining the cleaning solution are carried out through different draining pipes connected to the vessel.

6. (Original) The method of claim 4, wherein the pressurized gas is nitrogen gas.

7. (Original) The method of claim 4, wherein the etching solution is Oxalic acid solution or diluted Oxalic acid solution.

8. (Original) The method of claim 4, wherein the cleaning solution is deionized water.
9. (Previously Presented) The method of claim 4, wherein the step of forcing out the etching solution is enhanced by pumping the etching solution out of the vessel.
10. (Previously Presented) The method of claim 4, further comprising:
drying the objects by providing drying gas into the vessel after draining the cleaning solution.
11. (Previously Presented) The method of claim 10, wherein the drying gas includes isopropyl alcohol.
12. (New) The method of claim 4, wherein the step of cleaning the objects by introducing the cleaning solution into the vessel from below the objects is performed after the step of introducing the pressurized gas into the vessel from above the objects to force the etching solution out of the vessel from below the objects.
13. (New) A method of etching and cleaning objects contained in a vessel, comprising the steps of:
etching the objects with an etching solution in the vessel;
forcing the etching solution out of the vessel from below the objects by introducing a pressurized gas into the vessel from above the objects;

after the etching solution is forced out by the pressurized gas, cleaning the objects by introducing a cleaning solution into the vessel from below the objects; and
draining the cleaning solution from the vessel from above the objects.

14. (New) The method of claim 13, wherein the sequential steps of forcing out the etching solution alone and draining the cleaning solution are carried out through different draining pipes connected to the vessel.

15. (New) The method of claim 13, wherein the pressurized gas is nitrogen gas.

16. (New) The method of claim 13, wherein the etching solution is Oxalic acid solution or diluted Oxalic acid solution.

17. (New) The method of claim 13, wherein the cleaning solution is deionized water.

18. (New) The method of claim 13, wherein the step of forcing out the etching solution is enhanced by pumping the etching solution out of the vessel.

19. (New) The method of claim 13, further comprising:
drying the objects by providing drying gas into the vessel after draining the cleaning solution.

Application No.: 09/727,516
Reply to Office Action of October 5, 2005

Attorney Docket No. 3430-0149P
Amendment dated February 6, 2006
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20. (New) The method of claim 19, wherein the drying gas includes isopropyl alcohol.